

10528548_CLS1.txt
Most Frequently Occurring Classifications of Patents Returned
From A Search of 10528548 on June 06, 2006

Original Classifications

3 430/296
3 430/5
3 430/619
2 378/34
2 430/215
2 430/270.1
2 430/363
2 430/505

Cross-Reference Classifications

4 430/269
4 430/311
3 250/492.1
3 250/492.2
3 430/323
3 430/531
3 430/604
3 430/967
2 250/492.3
2 257/E21.032
2 257/E21.242
2 257/E21.346
2 257/E21.407
2 257/E21.454
2 430/203
2 430/236
2 430/296
2 430/320
2 430/321
2 430/325
2 430/326
2 430/5
2 430/505
2 430/535
2 430/536
2 430/617
2 430/945
2 430/955
2 430/957
2 430/961
2 435/320.1
2 435/325

Combined Classifications

5 430/269
5 430/296
5 430/5
4 250/492.2
4 430/311
4 430/505
3 250/492.1
3 250/492.3
3 430/203
3 430/215
3 430/270.1
3 430/323
3 430/363
3 430/531

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3 430/604
3 430/619
3 430/967
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2 257/E21.242
2 257/E21.346
2 257/E21.407
2 257/E21.454
2 378/34
2 430/236
2 430/320
2 430/321
2 430/325
2 430/326
2 430/533
2 430/535
2 430/536
2 430/617
2 430/945
2 430/955
2 430/957
2 430/961
2 435/320.1
2 435/325
2 438/571

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Titles of Most Frequently Occurring Classifications of Patents Returned
From A Search of 10528548 on June 06, 2006

5 430/269 (1 OR, 4 XR)
class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT

5 430/296 (3 OR, 2 XR)
class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/296 .Electron beam imaging

5 430/5 (3 OR, 2 XR)
class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/4 RADIATION MODIFYING PRODUCT OR PROCESS OF
MAKING
430/5 .Radiation mask

4 250/492.2 (1 OR, 3 XR)
class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.2 .Irradiation of semiconductor devices

4 430/311 (0 OR, 4 XR)
class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/311 .Making electrical device

4 430/505 (2 OR, 2 XR)
class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/495.1 RADIATION SENSITIVE PRODUCT
430/502 .Two or more radiation-sensitive layers
containing other than that characterized by the
composition
430/503 ..Layers sensitive to different spectral
regions
430/505 ...Developing inhibitor or processing
ingredient containing

3 250/492.1 (0 OR, 3 XR)
class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL

3 250/492.3 (1 OR, 2 XR)
class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.3 .Ion or electron beam irradiation

3 430/203 (1 OR, 2 XR)
class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,

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430/199 COMPOSITION, OR PRODUCT THEREOF
TRANSFER PROCEDURE BETWEEN IMAGE AND IMAGE
LAYER, IMAGE RECEIVING LAYERS, OR ELEMENT CONTAINING AN
IMAGE RECEIVING LAYER OR AN INGREDIENT FOR FORMING AN
IMAGE

430/202 RECEIVING LAYER
.Diffusion transfer process, element, or
identified image receiving layers therefor

430/203 ..By uniform application of heat, element, or
image receiving layer therefor

3 430/215 (2 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/199 TRANSFER PROCEDURE BETWEEN IMAGE AND IMAGE
LAYER, IMAGE RECEIVING LAYERS, OR ELEMENT CONTAINING
AN IMAGE RECEIVING LAYER OR AN INGREDIENT FOR FORMING AN
IMAGE

430/202 RECEIVING LAYER
.Diffusion transfer process, element, or
identified image receiving layers therefor

430/211 ..Element or identified image receiving layers
for dye image formation

430/212 ...Element containing silver salt sensitizer or
either element or image receiving layer for use
therewith

430/215Identified synthetic polymeric binder
contained in nonradiation sensitive processing
composition
permeable layer other than an image receiving or
neutralizing layer

3 430/270.1 (2 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/270.1 .Radiation sensitive composition or product or
process of making

3 430/323 (0 OR, 3 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/322 .Forming nonplanar surface
430/323 ..Including etching substrate

3 430/363 (2 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/357 COLOR IMAGING PROCESS
430/363 .Laser or radiation exposure other than visible
light

3 430/531 (0 OR, 3 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/495.1 RADIATION SENSITIVE PRODUCT

430/523 . Identified backing or protective layer containing

430/531 .. Synthetic resin or cellulose derivative containing

3 430/604 (0 OR, 3 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF

430/495.1 RADIATION SENSITIVE PRODUCT

430/564 . Silver compound sensitizer containing

430/599 .. Hypersensitizing or latensifying ingredient containing

430/604 ... Heavy metal or compound thereof

3 430/619 (3 OR, 0 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF

430/495.1 RADIATION SENSITIVE PRODUCT

430/564 . Silver compound sensitizer containing

430/617 .. Silver compound other than halide, per se, or composition for thermographic process process

430/618 ... Organic silver compound containing

430/619 And inorganic silver compound

3 430/967 (0 OR, 3 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF

430/966 X-RAY

430/967 . X-ray exposure process

2 250/491.1 (1 OR, 1 XR)

Class 250 : RADIANT ENERGY

250/491.1 MEANS TO ALIGN OR POSITION AN OBJECT RELATIVE TO A SOURCE OR DETECTOR

2 257/E21.032 (0 OR, 2 XR)

Class 257 : ACTIVE SOLID-STATE DEVICES

257/E21.001 PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE OR TREATMENT OF SEMICONDUCTOR OR SOLID-STATE DEVICES

OR OF

PARTS THEREOF (EPO)

257/E21.002 . Manufacture or treatment of semiconductor device (EPO)

257/E21.023 .. Making mask on semiconductor body for further photolithographic processing (EPO)

257/E21.024 ... Comprising organic layer (EPO)

257/E21.026 Characterized by treatment of photoresist layer (EPO)

257/E21.032 Ion lithographic process (EPO)

2 257/E21.242 (0 OR, 2 XR)

Class 257 : ACTIVE SOLID-STATE DEVICES

257/E21.001 PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE OR TREATMENT OF SEMICONDUCTOR OR SOLID-STATE DEVICES

OR OF

PARTS THEREOF (EPO)

257/E21.002 . Manufacture or treatment of semiconductor device (EPO)

257/E21.04 .. Device having at least one potential-jump barrier or surface barrier, e.g., PN junction, depletion

layer, carrier concentration layer (EPO)

257/E21.085 ... Device having semiconductor body comprising

Group IV elements or Group III-V compounds with or without

material on material, or cutting (EPO)

257/E21.211Treatment of semiconductor body using process other than deposition of semiconductor a substrate, diffusion or alloying of impurity radiation treatment (EPO)

257/E21.214To change their surface-physical characteristics or shape, e.g., etching, polishing, (EPO)

257/E21.24To form insulating layer thereon, e.g., for masking or by using photolithographic technique

257/E21.241Post-treatment (EPO)

257/E21.242Of organic layer (EPO)

2 257/E21.346 (0 OR, 2 XR)

Class 257 : ACTIVE SOLID-STATE DEVICES

257/E21.001 PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE OR TREATMENT OF SEMICONDUCTOR OR SOLID-STATE DEVICES OR OF

depletion without

257/E21.002 .Manufacture or treatment of semiconductor device (EPO)

257/E21.04 ..Device having at least one potential-jump barrier or surface barrier, e.g., PN junction, layer, carrier concentration layer (EPO)

257/E21.085 ...Device having semiconductor body comprising Group IV elements or Group III-V compounds with or without

impurities, e.g., doping materials (EPO)

257/E21.328Radiation treatment (EPO)

257/E21.331With high-energy radiation (EPO)

257/E21.334Producing ions for implantation (EPO)

257/E21.346Using mask (EPO)

2 257/E21.407 (0 OR, 2 XR)

Class 257 : ACTIVE SOLID-STATE DEVICES

257/E21.001 PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE OR TREATMENT OF SEMICONDUCTOR OR SOLID-STATE DEVICES OR OF

depletion without

257/E21.002 .Manufacture or treatment of semiconductor device (EPO)

257/E21.04 ..Device having at least one potential-jump barrier or surface barrier, e.g., PN junction, layer, carrier concentration layer (EPO)

257/E21.085 ...Device having semiconductor body comprising Group IV elements or Group III-V compounds with or without

impurities, e.g., doping materials (EPO)

257/E21.394Multi-step process for the manufacture of unipolar device (EPO)

257/E21.4Field-effect transistor (EPO)

257/E21.405Active layer is Group III-V compound, e.g., III-V velocity modulation transistor (VMT), NERFET (EPO)

257/E21.407with an heterojunction interface channel
or gate, e.g., HFET, HIGFET, SI SFET, HJFET, HEMT (EPO)

2 257/E21.454 (0 OR, 2 XR)

Class 257 : ACTIVE SOLID-STATE DEVICES

257/E21.001 PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE
OR TREATMENT OF SEMICONDUCTOR OR SOLID-STATE

DEVICES OR OF

PARTS THEREOF (EPO)

257/E21.002 Manufacture or treatment of semiconductor
device (EPO)

depletion

257/E21.04 ..Device having at least one potential-jump
barrier or surface barrier, e.g., PN junction,
layer, carrier concentration layer (EPO)

without

257/E21.394Multi-step process for the manufacture of
unipolar device (EPO)

257/E21.4Field-effect transistor (EPO)

257/E21.45With Schottky gate, e.g., MESFET (EPO)

257/E21.451Active layer being Group III-V compound
(EPO)

257/E21.452Lateral single-gate transistors (EPO)

257/E21.454Process wherein final gate is made
before formation, e.g., activation anneal, of source and
drain regions in active layer (EPO)

2 378/34 (2 OR, 0 XR)

Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES

378/1 SPECIFIC APPLICATION

378/34 .Lithography

2 430/236 (0 OR, 2 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/199 TRANSFER PROCEDURE BETWEEN IMAGE AND IMAGE
LAYER, IMAGE RECEIVING LAYERS, OR ELEMENT CONTAINING

AN

IMAGE

IMAGE RECEIVING LAYER

430/202 .Diffusion transfer process, element, or
identified image receiving layers therefor

430/235 ..Dye image formation process

430/236 ...Using silver salt sensitizer

2 430/320 (0 OR, 2 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT

430/320 .Making named article

2 430/321 (0 OR, 2 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF

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RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT

430/320 .Making named article
430/321 ..Optical device

2 430/325 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/322 .Forming nonplanar surface
430/325 ..Post image treatment to produce elevated
pattern

2 430/326 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR
OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/322 .Forming nonplanar surface
430/325 ..Post image treatment to produce elevated
pattern
430/326 ...Pattern elevated in radiation unexposed
areas

2 430/533 (1 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/495.1 RADIATION SENSITIVE PRODUCT
430/523 .Identified backing or protective layer
containing
430/531 ..Synthetic resin or cellulose derivative
containing
430/533 ...Polyester or polycarbonate

2 430/535 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/495.1 RADIATION SENSITIVE PRODUCT
430/523 .Identified backing or protective layer
containing
430/531 ..Synthetic resin or cellulose derivative
containing
430/533 ...Polyester or polycarbonate
430/534Next to polymer of unsaturated monomer
430/535Polymer of unsaturated ester or halide

2 430/536 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/495.1 RADIATION SENSITIVE PRODUCT
430/523 .Identified backing or protective layer
containing
430/531 ..Synthetic resin or cellulose derivative
containing
430/536 ...Polymer of unsaturated monomer

2 430/617 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

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430/495.1 RADIATION SENSITIVE PRODUCT
430/564 .Silver compound sensitizer containing
430/617 ..Silver compound other than halide, per se, or
composition for thermographic process process

2 430/945 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/945 LASER BEAM

2 430/955 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/955 PRECURSOR COMPOUND

2 430/957 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/955 PRECURSOR COMPOUND
430/957 .Development inhibitor releaser (DIR)

2 430/961 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/961 PROTECTIVE OR ANTIABRASION LAYER

2 435/320.1 (0 OR, 2 XR)
Class 435 : CHEMISTRY: MOLECULAR BIOLOGY AND MICROBIOLOGY
435/320.1 VECTOR, PER SE (E.G., PLASMID, HYBRID PLASMID,
COSMID, VIRAL VECTOR, BACTERIOPHAGE VECTOR, ETC.)
BACTERIOPHAGE VECTOR, ETC.)

2 435/325 (0 OR, 2 XR)
Class 435 : CHEMISTRY: MOLECULAR BIOLOGY AND MICROBIOLOGY
435/325 ANIMAL CELL, PER SE (E.G., CELL LINES, ETC.);
COMPOSITION THEREOF; PROCESS OF PROPAGATING, MAINTAINING
OR
PRESERVING AN ANIMAL CELL OR COMPOSITION THEREOF; PROCESS
OF ISOLATING OR SEPARATING AN ANIMAL CELL OR COMPOSITION
THEREOF; PROCESS OF PREPARING A COMPOSITION CONTAINING AN
ANIMAL CELL; CULTURE MEDIA THEREFORE

2 438/571 (1 OR, 1 XR)
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
438/570 FORMING SCHOTTKY JUNCTION (I.E.,
SEMICONDUCTOR-CONDUCTOR RECTIFYING JUNCTION CONTACT)
438/571 .Combined with formation of ohmic contact to
semiconductor region